

SPIN150i spin coater

The single wafer spin coater SPIN150i is available in NPP or PTFE. These high quality spin coaters are specifically designed for R&D and low volume production in the MEMS, Semiconductor, PV, Microfluidic fields, etc. Suitable for all typical spin processes: cleaning, rinse/dry, coating, developing and etching.

Each Fab, R&D or even each student in university uses different spin processes. POLOS spin coaters offer unlimited processes: easy, step-by-step recipe programming via a large color touchscreen controller, USB up- or download from your own PC, unlimited programs / steps and graphical representation. And a repeatable spin coating process, time and time again. This makes the



POLOS SPIN150i the best laboratory spin coater you can buy! The SPIN150i for up to 150 mm substrates includes a vacuum chuck A-V36 and fragment adapter D-V10. A variety of nozzles, megasonic cleaning and dispense lines can be added as options. The low-cost SPIN150i spin coater is suitable for processing fragments as small as 5 mm up to Ø150 mm (or 6") or 4" x 4" substrates.

Item	Specifications
Housing material	Natural polypropylene (NPP)
Process chamber material	Natural polypropylene (NPP) or high chemical resistant PTFE (TFM™)
Interface	Detachable, full-size touchscreen, glove friendly, IP52, chemical resistant
External connection	1 USB port on the side of your display
Max. substrate diameter	160 mm round or 4" x 4" square
Max. process chamber diameter	202 mm
Dimension (desktop version)	274 (w) x 250 (h) x 451 (d) mm

Options SPIN150i & SPIN200i



Syringe holder starter kit consisting of 30cc dispense barrels, needles and plungers.



Center dispense system with higher reliability of results.



Centering tool is easy to use and adjustable for different substrate sizes.



Dispense unit can be mounted in syringe holder and be connected to one of the 3 programmable dry contacts.

SPIN200i spin coater

The single wafer spin coater SPIN200i is an advanced system that offers precise, repeatable process control. An aerodynamically efficient chamber enhances uniformity, while the natural polypropylene or PTFE construction ensures a metal-free, contamination-free process area that is easy to clean.

The SPIN200i comes with a chuck that will hold from 4" to 8" wafers. This spin coater offers exceptional value and capability: precision speed range of up to 12,000 rpm, programmable in 1 rpm, for CW, CCW rotation (ideal for "puddle" develop), and per-step acceleration of max. 30,000. It is also programmable in 1 rpm, to cover any process requirement. It is programmed through an easy-



entry color touchscreen. The self-explanatory icons make it easy to operate even for new users.

A quality choice for the long-term, all our spinners are designed and manufactured in Germany.

Item	Specifications
Housing material	Natural polypropylene (NPP)
Process chamber material	Natural polypropylene (NPP) or high chemical resistant PTFE (TFM™)
Interface	Detachable, full-size touchscreen, glove friendly, IP52, chemical resistant
External connection	1 USB port on the side of your display
Max. substrate diameter	260 mm round or 6" x 6" square
Max. process chamber diameter	302 mm
Dimension (desktop version)	380 (w) x 307 (h) x 599 (d) mm

Options SPIN150i & SPIN200i



Liners are available in PET. 0.5mm thick, transparent, antistatic (108 - 1010 Ω) to prevent possible build-up of static charge in the chamber.



Central Dispensing Syringe Holder for single or triple syringes, with integrated N2 diffuser.



Corrugated Drainhose and connector in NPP, including connection to connect to the drainport.



Foot Switch for hand free usage; controlling start/stop function and vacuum.